



Docket No.: 09852/0205523-US0
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hideki Fujiwara et al.

Application No.: 10/599,440

Confirmation No.: 8901

Filed: September 28, 2006

Art Unit: 1792

For: SILICON ELECTRODE PLATE FOR PLASMA
ETCHING WITH SUPERIOR DURABILITY

Examiner: A. M. Crowell

AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Madam:

INTRODUCTORY COMMENTS

In response to the Office Action dated March 5, 2009, please amend the above-identified U.S. patent application as follows:

Listing of the Claim begins on page 2 of this paper.

Remarks/Arguments begin on page 3 of this paper.